

REMARKS

At the outset, the Examiner is thanked for the thorough review and consideration of the pending application. The Office Action dated April 19, 2005 has been received and its contents carefully reviewed.

By this Response, Applicant amends claims 1, 13 and 24-2 and cancels claims 2 and 14 without prejudice or disclaimer. Accordingly, claims 1, 3-13 and 15-26 are currently pending. Reexamination and reconsideration of the pending claims is respectfully requested.

In the Office Action, the Examiner rejected claims 1, 2, 5, 11-14, 17, 22-23 and 25-26 under 35 U.S.C. § 102(b) as being anticipated by Ito et al. (U.S. Patent No. 6,437,497); rejected claims 3, 4, 15, 16 and 24 under 35 U.S.C. § 103(a) as being unpatentable over Ito et al. in view of Hayashi et al. (U.S. Patent No. 6,051,918); rejected claims 6, 7, 18 and 19 under 35 U.S.C. § 103(a) as being unpatentable over Ito et al. in view of Nakagawa et al. (U.S. Patent No. 6,208,067); and rejected claims 6, 8, 9, 18, 20 and 21 under 35 U.S.C. § 103(a) as being unpatentable over Ito et al. in view of Pyun et al. (U.S. Patent No. 6,680,565). Applicant respectfully traverses these rejections.

The rejection of claims 1, 2, 5, 11-14, 17, 22-23 and 25-26 under 35 U.S.C. § 102(b) as being anticipated by Ito et al. is respectfully traversed and reconsideration is requested.

Claim 1 is allowable over the cited references in that claim 1 recites a combination of elements including, for example, "...wherein a height of the skirt on the long side of the shadow mask is less than a height of the skirt on the short side of the shadow mask." None of the cited references including Ito et al., singly or in combination, teaches or suggests at least this feature of the claimed invention.

Applicant respectfully submits that the present invention is directed to "a cathode ray tube having a shadow mask for obviating doming phenomenon." See paragraph [0002] of the present application. Further, paragraph [0049] of the present application discloses "the short side of the shadow mask is more susceptible to the doming phenomenon... the skirt length on the short side (YS) is made to be relatively longer than the skirt length on the long side (XS) to reduce the doming phenomenon." Thus, the aforementioned feature recited in claim 1 is disclosed in the present invention, which is not taught by any of the cited references.

Accordingly, Applicant respectfully submits that claim 1 and claims 3-12, which depend therefrom, are allowable over the cited references.

Claim 13 is allowable over the cited references in that claim 13 recites a combination of elements including, for example, "...wherein a height of the skirt on the long side of the shadow mask is less than a height of the skirt on the short side of the shadow mask." None of the cited references including Ito et al., singly or in combination, teaches or suggests at least this feature of the claimed invention. Accordingly, Applicant respectfully submits that claim 13 and claims 15-23, which depend therefrom, are allowable over the cited references.

Claim 25 is allowable over the cited references in that claim 25 recites a combination of elements including, for example, "...wherein a height of the skirt on the long side of the shadow mask is less than a height of the skirt on the short side of the shadow mask." None of the cited references including Ito et al., singly or in combination, teaches or suggests at least this feature of the claimed invention. Accordingly, Applicant respectfully submits that claim 25 is allowable over the cited references.

Claim 26 is allowable over the cited references in that claim 26 recites a combination of elements including, for example, "...wherein a height of the skirt on the long side of the shadow mask is less than a height of the skirt on the short side of the shadow mask." None of the cited references including Ito et al., singly or in combination, teaches or suggests at least this feature of the claimed invention. Accordingly, Applicant respectfully submits that claim 26 is allowable over the cited references.

The rejection of claims 3, 4, 15, 16 and 24 under 35 U.S.C. § 103(a) as being unpatentable over Ito et al. in view of Hayashi et al. is respectfully traversed and reconsideration is requested.

Claim 24 is allowable over the cited references in that claim 24 recites a combination of elements including, for example, "...wherein a height of the skirt on the long side of the shadow mask is less than a height of the skirt on the short side of the shadow mask." None of the cited references including Ito et al., singly or in combination, teaches or suggests at least this feature of the claimed invention. Accordingly, Applicant respectfully submits that claim 24 is allowable over the cited references.

As discussed above with respect to the rejection of claims 1 and 13, since Hayashi et al. fails to cure the deficiencies of Ito et al., Applicant respectfully requests that claims 3, 4, 15 and 16 are allowable over the cited references.

The rejection of claims 6, 7, 18 and 19 under 35 U.S.C. § 103(a) as being unpatentable over Ito et al. in view of Nakagawa et al. is respectfully traversed and reconsideration is requested. As discussed above with respect to the rejection of claims 1 and 13, since Nakagawa et al. fails to cure the deficiencies of Ito et al., Applicant respectfully requests that claims 6, 7, 18 and 19 are allowable over the cited references.

The rejection of 6, 8, 9, 18, 20 and 21 under 35 U.S.C. § 103(a) as being unpatentable over Ito et al. in view of Pyun et al. is respectfully traversed and reconsideration is requested. As discussed above with respect to the rejection of claims 1 and 13, since Pyun et al. fails to cure the deficiencies of Ito et al., Applicant respectfully requests that claims 6, 8, 9, 18, 20 and 21 are allowable over the cited references.

Applicant believes the application is in condition for allowance and early, favorable action is respectfully solicited. If for any reason the Examiner finds the application other than in condition for allowance, the Examiner is requested to call the undersigned attorney at (202) 496-7500 to discuss the steps necessary for placing the application in condition for allowance. All correspondence should continue to be sent to the below-listed address.

If these papers are not considered timely filed by the Patent and Trademark Office, then a petition is hereby made under 37 C.F.R. § 1.136, and any additional fees required under 37 C.F.R. § 1.136 for any necessary extension of time, or any other fees required to complete the filing of this response, may be charged to Deposit Account No. 50-0911. Please credit any overpayment to deposit Account No. 50-0911. A duplicate copy of this sheet is enclosed.

Dated: May 31, 2005

Respectfully submitted,

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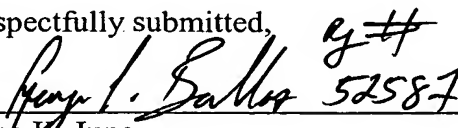
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